

TSMC-99-646B



#3/98K9A07  
Saile

July 17, 2001

To: Commissioner of Patents and Trademarks  
Washington, D.C. 20231

Fr: George O. Saile, Reg. No. 19,572  
20 McIntosh Drive  
Poughkeepsie, N.Y. 12603

Subject:

Serial No. 09/846,536 05/02/01

Wen-Ting Chu, Hsin-Ming Chen

A NOVEL SELF-ALIGNED, LOW CONTACT  
RESISTANCE, VIA FABRICATION PROCESS

Grp. Art Unit: 2811

TC 2800 MAIL ROOM  
JUL 20 2001

RECEIVED

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation  
In An Application.

The following Patents and/or Publications are submitted to  
comply with the duty of disclosure under CFR 1.97-1.99 and  
37 CFR 1.56. Copies of each document is included herewith.

U.S. Patent 5,834,369 to Murakami et al., "Method of  
Preventing Diffusion Between Interconnect and Plug", discloses  
a method for a Al line over an W-plug.

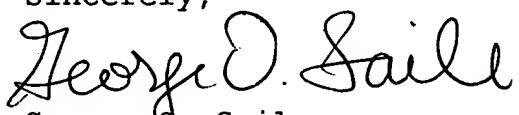
U.S. Patent 5,994,213 to Wang et al., "Aluminum Plug  
Process", teaches an Al plug process.

U.S. Patent 5,956,609 to Lee et al., "Method for Reducing Stress and Improving Step-Coverage of Tungsten Interconnects and Plugs", discusses a plug/line process.

U.S. Patent 5,472,912 to Miller, "Method of Making an Integrated Circuit Structure by Using a Non-Conductive Plug", discloses a non-conductive plug that partially fills the via hole.

U.S. Patent 5,913,143 to Harakawa, "Method of Making a MultiLayer Interconnection of Semiconductor Device Using Plug", discusses an inter-level insulating film formed on a first Al film and a contact hole formed to partly expose the first Al film.

Sincerely,

  
George O. Saile,  
Reg. No. 19572



Form PTO-1449

INFORMATION DISCLOSURE CITATION  
IN AN APPLICATION

(Use several sheets if necessary)

Doctor's Number (Optional)

TSMC-99-046B

Lexicon Hanover

09/846,536

Amherst

Wen-Ting Chu et al.

Filing Date

05/02/01

Groups and Un

2811

U. S. PATENT DOCUMENTS

## FOREIGN PATENT DOCUMENTS

**OTHER DOCUMENTS** (Including Author, Title, Date, Portion Page, Etc.)

DUNNER

on

DATE CONSIDERED

11 / 16 / 01

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through